

# The 42nd International Conference of Photopolymer Science and Technology (ICPST-42)

Materials & Processes for Advanced Lithography,  
Nanotechnology and Phototechnology

**Venue: Arcrea Himeji (Convention Center),  
Himeji City, Hyogo, Japan**

<http://www.spst-photopolymer.org>



**Conference in person**

**June 24 - 27, 2025**

The International Conference of Photopolymer Science and Technology (ICPST) organized by the Society of Photopolymer Science and Technology (SPST) for these 40 years has played an important role as a world-wide forum for discussion and information exchange on the resist material process technology used in various lithographic technologies such as g-line, i-line, KrF, ArF, electron beam, and X-ray. ArF immersion lithography is currently used for 22-nm-generation semiconductor manufacturing technology. In 2019, EUV lithography has started to be used in HVM of 7-nm-node-logic devices for smart phones. And EUV lithography, nanoimprint lithography, and DSA technology are promising candidates for the semiconductor nano-fabrication technologies in next 1 nm node and beyond. At the International Electron Devices Meeting (IEDM) 2024, several chip manufacturers reported that advanced lithography is required in the future for the mass production of semiconductor devices continuously. For supporting the future IoT technology, advanced techniques of the lithography are required increasingly, where material technologies such as photo-functional groups, photo-acid generators, photo-curable resins, etc. are the driving force for the progress of semiconductor technology with quantum scale and quantum effect. Basic research on photopolymer is more significant in developing new technologies such as quantum device technology with lower power consumption and lower manufacturing cost by combining with life science and quantum device technology. New Symposia will continue to be provided in place of conventional ones. The international symposium of Organic Solar Cells – Materials, Device Physics, and Processes was added in 2017. In addition, the international symposium of Fundamentals and Applications of Biomimetics Materials and Processes was added in 2018. Constructive opinions from researchers and scientists are welcomed for future progress of ICPST. **The venue is moved to Arcrea Himeji (convention Center), Himeji City, Hyogo, Japan, which is located near the JR Himeji Station.** The Shinkansen (high speed train) stops at JR Himeji Station. The detailed transportation information to the Arcrea Himeji is listed at the home page of ICPST-42.

# Scopes

## A. English Symposia

- A0. Plenary Talk
- A1. Next Generation Lithography, EB Lithography and Nanotechnology
- A2. Nanobiotechnology
- A3. Directed Self Assembly (DSA)
- A4. Computational / Analytical Approach for Lithography Processes
- A5. EUV Lithography
- A6. Nanoimprint
- A7. 193 nm Lithography Extension
- A8. Photopolymers in 3-D Printing/ Additive Manufacturing
- A9. Strategies and Materials for Advanced Packaging, Next Generation MEMS, Flexible Devices
- A10. Chemistry for Advanced Photopolymer Science
- A11. Organic and Hybrid Materials for Photovoltaic and Optoelectronic Devices
- A12. Fundamentals and Applications of Biomimetics Materials and Processes
- A13. Polyimides and High Thermally Stable Resins
- A14. General Scopes of Photopolymer Science and Technology

## P. Panel Symposium

## B. Japanese Symposia

- B1. Polyimides and High Thermally Stable Resins  
-Functionalization and Practical Applications-
- B2. Plasma Photochemistry and Functionalization of Polymer Surfaces
- B3. General Scopes of Photopolymer Science and Technology

## C. Tutorial Session

Under consideration

**NOTICE:** All symposia will be held in person only.  
Tutorial will be held in person and online.

## Schedule (tentative)

June 27		June 28	June 29	June 30
		Registration (9:00-17:00)	Registration (9:00-17:00)	Registration (9:00-15:00)
		Opening remarks (9:30-9:45)	Scientific program (9:00-18:00)	Scientific program (9:00-18:20)
		Plenary Talk (9:45-10:35)		
Tutorial 13:00-17:00	Registration (15:00-17:00)	Scientific program (10:35-18:50)	PST Award Ceremony (17:25-17:55)	
	Welcome Reception (17:00-19:00)	Panel symposium (19:00-20:30)	Banquet (18:00-20:00)	Closing remarks (18:20-18:30)

**Registration** (<https://www.spst-photopolymer.org/conference/registration/>)

Category	Early bird (until May 31, 2025, JST)	Late and on-site (from June 1, 2025, JST)
Government, academia and industries	65,000 JPY	80,000 JPY
Students	10,000 JPY	15,000 JPY
*In consideration of the recent rise in prices and ongoing operations, SPST has decided the membership fees. Banquet	5,000 JPY	5,000 JPY

## Papers (<https://www.spst-photopolymer.org/journal/>)

Papers submitted to ICPST-42 are published in Journal of Photopolymer Science and Technology, Vol. 38, No. 1-5 (2025). Please submit your manuscript before April 1, 2025 from the URL.

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